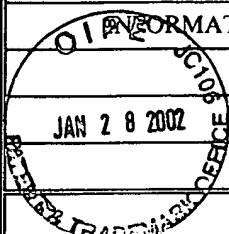

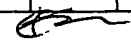


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| U.S. Department of Commerce, Patent and Trademark Office | | | | Atty Docket No. | | Serial No. | | |
| | | | | M-9455 US | | 09/670,000 | | |
| <div style="text-align: center;">  <p>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</p> <p>(Use several sheets if necessary)</p> </div> | | | | Applicants | | | | |
| | | | | James M. Holden et al. | | | | |
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